

Wet Bench - RCA MOS Clean



Facts

This wet bench is configured to perform the RCA Cleaning Process

- Used for MOS grade wafers prior to gate oxidation.
 - No gold, copper, other trap inducing materials.
- Bench is configured with a heated quartz tank for SC1 Clean or APM (Ammonia/peroxide mix) and a heated quartz tank for a SC2 Clean or HPM (Hydrochloric / Hydrogen Peroxide mix).
- A 50:1 HF tank is in the bench for native oxide removal.
- Rinse tanks for each process step are also in the bench.
- The wetbench also has a heated quartz bath for Piranha Cleans .

Personnel

- Tool Engineer -
- Process Engineer - Sean O'Brien
- Process Engineer - Patricia Meller

Tool & Process Information

- Wet Chemical Processing Information

Manuals & Users

- MOS RCA Bench Manual
- MOS RCA Wetbench Certification Checklist